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LIST OF REFERENCES CITED BY APPLICANT

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YOSHIAKI SAITO, ET AL.

FILED

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TTN	AA	5,659,499	08/19/97	E. Chen, et al.			
	AB	5,956,267	09/21/99	A. T. Hurst, et al.			
	AC	5,940,319	08/17/99	M. Durlam, et al.			
	AD	6,178,074	01/2001	Gill			
	AE	6,233,172	05/2001	Chen et al.			
	AF	5,173,873	12/1992	Wu et al.			
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	AH	6,054,734	04/2000	Aozana et al.			
	AI	6,205,052	03/2001	Slaughter et al.			
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	AK	5,768,181	06/1998	Zhu et al.			
	AL	5,838,608	11/1998	Zhu et al.			
TTN	AM	6,072,718	06/2000	Abraham et al.			
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
TTN	AO	WO 00/10172	02/24/00	WIPO (with English abstract)		x
TTN	AP	10-4227	01/06/98	Japan		x
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

TTN	AW	J.S. MOODERA, et al., J. Appl. Phys., Vol. 79, No. 8, pps. 4724-4729, "FERROMAGNETIC-INSULATOR-FERROMAGNETIC TUNNELING: SPIN-DEPENDENT TUNNELING AND LARGE MAGNETORESISTANCE IN TRILAYER JUNCTIONS (INVITED)," April 15, 1996
TTN	AX	L.F. SCHELP, et al., Physical Review B, Vol. 56, No. 10, pps. R5747 - R5750, "SPIN-DEPENDENT TUNNELING WITH COULOMB BLOCKADE," September 1, 1997
TTN	AY	Y. SAITO, et al., J. Magnetic. Soc., Vol. 23, No. 4-2, pps. 1269-1272, "SPIN-DEPENDENT TUNNELING THROUGH LAYERED HARD-MAGNETIC NANO-PARTICLES," 1999
TTN	AZ	F. MONTAIGNE, et al., Applied Physics Letters, Vol. 73, No. 19, pps. 2829-2831, "ENHANCED TUNNEL MAGNETORESISTANCE AT HIGH BIAS VOLTAGE IN DOUBLE-BARRIER PLANAR JUNCTIONS," November 9, 1998

Examiner

Date Considered 6/14/04

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.